



*STW*

Docket No. 244747US0X

IN RE APPLICATION OF: Kazuo NISHIMOTO, et al.

SERIAL NO: 10/694,890

FILED: October 29, 2003

FOR: AQUEOUS DISPERSION FOR CHEMICAL MECHANICAL POLISHING, CHEMICAL MECHANICAL POLISHING PROCESS, PRODUCTION PROCESS OF SEMICONDUCTOR DEVICE AND MATERIAL FOR PREPARING AN AQUEOUS DISPERSION FOR CHEMICAL MECHANICAL POLISHING

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

Transmitted herewith is an amendment in the above-identified application.

- ☒ No additional fee is required
- ☐ Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.
- ☐ Additional documents filed herewith:

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	8	MINUS	23	0	x \$50 =	\$0.00
INDEPENDENT	1	MINUS	3	0	x \$200 =	\$0.00
		<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS			+ \$360 =	\$0.00
		TOTAL OF ABOVE CALCULATIONS				\$0.00
		<input type="checkbox"/> Reduction by 50% for filing by Small Entity				\$0.00
		<input type="checkbox"/> Recordation of Assignment			+ \$40 =	\$0.00
		TOTAL				\$0.00

- ☐ A check in the amount of **\$0.00** is attached.
- ☐ Credit card payment form is attached to cover the fees in the amount of **\$0.00**
- ☒ Please charge any additional Fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.
- ☒ If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon

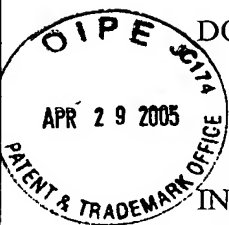
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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

:

KAZUO NISHIMOTO, ET AL.

: EXAMINER: MARCHESCHI, M. A.

SERIAL NO: 10/694,890

:

FILED: OCTOBER 29, 2003

: GROUP ART UNIT: 1755

FOR: AQUEOUS DISPERSION FOR  
CHEMICAL MECHANICAL POLISHING,  
CHEMICAL MECHANICAL POLISHING  
PROCESS, PRODUCTION PROCESS OF  
SEMICONDUCTOR DEVICE AND  
MATERIAL FOR PREPARING AN  
AQUEOUS DISPERSION FOR  
CHEMICAL MECHANICAL POLISHING

:

AMENDMENT

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

Responsive to the Office Action dated February 4, 2005, Applicants respectfully request reconsideration of the above-identified application in view of the following amendment and remarks.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Discussion of the Amendment** begins on page 5 of this paper.

**Remarks** begin on page 6 of this paper.